Hyungjun Kim

List of Publications by Year
in descending order

280	12,882	20817 60	30922 102
papers	citations	h-index	g-index

293	293	293	17071
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	MoS₂ Nanosheet Phototransistors with Thickness-Modulated Optical Energy Gap. Nano Letters, 2012, 12, 3695-3700.	9.1	1,221
2	Applications of atomic layer deposition to nanofabrication and emerging nanodevices. Thin Solid Films, 2009, 517, 2563-2580.	1.8	533
3	Improvement of Gas-Sensing Performance of Large-Area Tungsten Disulfide Nanosheets by Surface Functionalization. ACS Nano, 2016, 10, 9287-9296.	14.6	351
4	Layer-Controlled, Wafer-Scale, and Conformal Synthesis of Tungsten Disulfide Nanosheets Using Atomic Layer Deposition. ACS Nano, 2013, 7, 11333-11340.	14.6	324
5	Dye-Sensitized MoS₂ Photodetector with Enhanced Spectral Photoresponse. ACS Nano, 2014, 8, 8285-8291.	14.6	268
6	Facile CO₂ Electro-Reduction to Formate via Oxygen Bidentate Intermediate Stabilized by High-Index Planes of Bi Dendrite Catalyst. ACS Catalysis, 2017, 7, 5071-5077.	11.2	263
7	Controllable synthesis of molybdenum tungsten disulfide alloy for vertically composition-controlled multilayer. Nature Communications, 2015, 6, 7817.	12.8	188
8	Exciton dynamics in atomically thin MoS<mml:math xmlns:mml="http://www.w3.org/1998/Math/MathML" display="inline"><mml:msub><mml:mrow /><mml:mn>2</mml:mn></mml:msub></mml:math>: Interexcitonic interaction and broadening kinetics. Physical Review B, 2013, 88, .	3.2	173
9	NiO Resistive Random Access Memory Nanocapacitor Array on Graphene. ACS Nano, 2010, 4, 2655-2658.	14.6	171
10	High performance thin film transistor with low temperature atomic layer deposition nitrogen-doped ZnO. Applied Physics Letters, 2007, 91, .	3.3	166
11	Synthesis of wafer-scale uniform molybdenum disulfide films with control over the layer number using a gas phase sulfur precursor. Nanoscale, 2014, 6, 2821.	5.6	166
12	Synthesis of carbon nanotubeâ€“nickel nanocomposites using atomic layer deposition for high-performance non-enzymatic glucose sensing. Biosensors and Bioelectronics, 2015, 63, 325-330.	10.1	150
13	Micropatternable Double-Faced ZnO Nanoflowers for Flexible Gas Sensor. ACS Applied Materials & Interfaces, 2017, 9, 32876-32886.	8.0	147
14	Low-temperature synthesis of 2D MoS₂ on a plastic substrate for a flexible gas sensor. Nanoscale, 2018, 10, 9338-9345.	5.6	142
15	Bifunctional 2D Superlattice Electrocatalysts of Layered Double Hydroxideâ€“Transition Metal Dichalcogenide Active for Overall Water Splitting. ACS Energy Letters, 2018, 3, 952-960.	17.4	140
16	ZnO thin films prepared by atomic layer deposition and rf sputtering as an active layer for thin film transistor. Thin Solid Films, 2008, 516, 1523-1528.	1.8	132
17	Gaâ€“Doped Ptâ€“Ni Octahedral Nanoparticles as a Highly Active and Durable Electrocatalyst for Oxygen Reduction Reaction. Nano Letters, 2018, 18, 2450-2458.	9.1	125
18	Roles of SnX₂ (X = F, Cl, Br) Additives in Tin-Based Halide Perovskites toward Highly Efficient and Stable Lead-Free Perovskite Solar Cells. Journal of Physical Chemistry Letters, 2018, 9, 6024-6031.	4.6	121

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19	Wafer-scale, conformal and direct growth of MoS2 thin films by atomic layer deposition. Applied Surface Science, 2016, 365, 160-165.	6.1	119
20	Polymeric Carbon Nitride with Localized Aluminum Coordination Sites as a Durable and Efficient Photocatalyst for Visible Light Utilization. ACS Catalysis, 2018, 8, 4241-4256.	11.2	118
21	Highly Uniform Atomic Layer-Deposited MoS₂@3D-Ni-Foam: A Novel Approach To Prepare an Electrode for Supercapacitors. ACS Applied Materials & Interfaces, 2017, 9, 40252-40264.	8.0	117
22	Improved Sensitivity in Schottky Contacted Two-Dimensional MoS₂ Gas Sensor. ACS Applied Materials & Interfaces, 2019, 11, 38902-38909.	8.0	117
23	A General Strategy to Atomically Dispersed Precious Metal Catalysts for Unravelling Their Catalytic Trends for Oxygen Reduction Reaction. ACS Nano, 2020, 14, 1990-2001.	14.6	116
24	Recovery Improvement for Large-Area Tungsten Diselenide Gas Sensors. ACS Applied Materials & Interfaces, 2018, 10, 23910-23917.	8.0	115
25	Fabrication of rough Al doped ZnO films deposited by low pressure chemical vapor deposition for high efficiency thin film solar cells. Current Applied Physics, 2010, 10, S459-S462.	2.4	110
26	Unipolar stroke, electroosmotic pump carbon nanotube yarn muscles. Science, 2021, 371, 494-498.	12.6	110
27	Intermetallic PtCu Nanoframes as Efficient Oxygen Reduction Electrocatalysts. Nano Letters, 2020, 20, 7413-7421.	9.1	109
28	The properties of plasma-enhanced atomic layer deposition (ALD) ZnO thin films and comparison with thermal ALD. Applied Surface Science, 2011, 257, 3776-3779.	6.1	108
29	Hydrophobicity of Rare Earth Oxides Grown by Atomic Layer Deposition. Chemistry of Materials, 2015, 27, 148-156.	6.7	106
30	Selective electrochemical reduction of nitric oxide to hydroxylamine by atomically dispersed iron catalyst. Nature Communications, 2021, 12, 1856.	12.8	106
31	2D Transition Metal Dichalcogenide Heterostructures for pâ€•and nâ€Type Photovoltaic Selfâ€Powered Gas Sensor. Advanced Functional Materials, 2020, 30, 2003360.	14.9	102
32	Static and Dynamic Performance of Complementary Inverters Based on Nanosheet Î±-MoTe₂ p-Channel and MoS₂ n-Channel Transistors. ACS Nano, 2016, 10, 1118-1125.	14.6	98
33	Activity Origin and Multifunctionality of Pt-Based Intermetallic Nanostructures for Efficient Electrocatalysis. ACS Catalysis, 2019, 9, 11242-11254.	11.2	96
34	Heteroepitaxial Ferroelectric ZnSnO₃ Thin Film. Journal of the American Chemical Society, 2009, 131, 8386-8387.	13.7	93
35	UVâ€“Visible Spectroscopic Analysis of Electrical Properties in Alkali Metalâ€Doped Amorphous Zinc Tin Oxide Thinâ€Film Transistors. Advanced Materials, 2013, 25, 2994-3000.	21.0	93
36	High-Performance Gas Sensor Using a Large-Area WS_{2x}Se_{2â€“2x} Alloy for Low-Power Operation Wearable Applications. ACS Applied Materials & Interfaces, 2018, 10, 34163-34171.	8.0	93

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37	On the importance of the electric double layer structure in aqueous electrocatalysis. Nature Communications, 2022, 13, 174.	12.8	92
38	High-Quality Cobalt Thin Films by Plasma-Enhanced Atomic Layer Deposition. Electrochemical and Solid-State Letters, 2006, 9, G323.	2.2	90
39	Exfoliated 2D Lepidocrocite Titanium Oxide Nanosheets for High Sulfur Content Cathodes with Highly Stable Liâ€“S Battery Performance. ACS Energy Letters, 2018, 3, 412-419.	17.4	90
40	High-Capacity, Self-Assembled Metalâ€“Oxideâ€“Semiconductor Decoupling Capacitors. IEEE Electron Device Letters, 2004, 25, 622-624.	3.9	89
41	Thermal and plasma enhanced atomic layer deposition ruthenium and electrical characterization as a metal electrode. Microelectronic Engineering, 2008, 85, 39-44.	2.4	89
42	Graphene as an atomically thin barrier to Cu diffusion into Si. Nanoscale, 2014, 6, 7503-7511.	5.6	89
43	Layer-modulated synthesis of uniform tungsten disulfide nanosheet using gas-phase precursors. Nanoscale, 2015, 7, 1308-1313.	5.6	86
44	Thermal and Plasma-Enhanced ALD of Ta and Ti Oxide Thin Films from Alkylamide Precursors. Electrochemical and Solid-State Letters, 2006, 9, G191.	2.2	83
45	Characteristics and applications of plasma enhanced-atomic layer deposition. Thin Solid Films, 2011, 519, 6639-6644.	1.8	83
46	Nanosheet thickness-modulated MoS₂dielectric property evidenced by field-effect transistor performance. Nanoscale, 2013, 5, 548-551.	5.6	83
47	Thermal Transformation of Molecular Ni²⁺â€“N₄ Sites for Enhanced CO₂ Electroreduction Activity. ACS Catalysis, 2020, 10, 10920-10931.	11.2	81
48	Distorted Carbon Nitride Structure with Substituted Benzene Moieties for Enhanced Visible Light Photocatalytic Activities. ACS Applied Materials & Interfaces, 2017, 9, 40360-40368.	8.0	80
49	Ru nanostructure fabrication using an anodic aluminum oxide nanotemplate and highly conformal Ru atomic layer deposition. Nanotechnology, 2008, 19, 045302.	2.6	79
50	Atomic Layer Deposition of Ni Thin Films and Application to Area-Selective Deposition. Journal of the Electrochemical Society, 2011, 158, D1.	2.9	79
51	Review of plasma-enhanced atomic layer deposition: Technical enabler of nanoscale device fabrication. Japanese Journal of Applied Physics, 2014, 53, 03DA01.	1.5	79
52	Mixed Valence Perovskite Cs₂Au₂I₆: A Potential Material for Thinâ€Film Pbâ€Free Photovoltaic Cells with Ultrahigh Efficiency. Advanced Materials, 2018, 30, e1707001.	21.0	79
53	Insight into the Microenvironments of the Metalâ€“Ionic Liquid Interface during Electrochemical CO₂ Reduction. ACS Catalysis, 2018, 8, 2420-2427.	11.2	77
54	Self-Limiting Layer Synthesis of Transition Metal Dichalcogenides. Scientific Reports, 2016, 6, 18754.	3.3	74

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55	Reaction Mechanism of Area-Selective Atomic Layer Deposition for Al₂O₃ Nanopatterns. ACS Applied Materials & Interfaces, 2017, 9, 41607-41617.	8.0	73
56	Photocatalytic functional coatings of TiO2 thin films on polymer substrate by plasma enhanced atomic layer deposition. Applied Catalysis B: Environmental, 2009, 91, 628-633.	20.2	70
57	The application of atomic layer deposition for metallization of 65 nm and beyond. Surface and Coatings Technology, 2006, 200, 3104-3111.	4.8	69
58	Synthesis of horizontally aligned ZnO nanowires localized at terrace edges and application for high sensitivity gas sensor. Applied Physics Letters, 2008, 93, .	3.3	67
59	High Quality Area-Selective Atomic Layer Deposition Co Using Ammonia Gas as a Reactant. Journal of the Electrochemical Society, 2010, 157, D10.	2.9	65
60	Evaluation of bone healing with eggshellâ€derived bone graft substitutes in rat calvaria: A pilot study. Journal of Biomedical Materials Research - Part A, 2008, 87A, 203-214.	4.0	63
61	Synthesis of Few-Layered Graphene Nanoballs with Copper Cores Using Solid Carbon Source. ACS Applied Materials & Interfaces, 2013, 5, 2432-2437.	8.0	62
62	Transfer and Dynamic Inversion of Coassembled Supramolecular Chirality through 2D-Sheet to Rolled-Up Tubular Structure. Journal of the American Chemical Society, 2017, 139, 17711-17714.	13.7	62
63	Improved Synapse Device With MLC and Conductance Linearity Using Quantized Conduction for Neuromorphic Systems. IEEE Electron Device Letters, 2018, 39, 312-315.	3.9	60
64	Dip-Pen Lithography of Ferroelectric PbTiO₃ Nanodots. Journal of the American Chemical Society, 2009, 131, 14676-14678.	13.7	57
65	Growth characteristics and electrical properties of La2O3 gate oxides grown by thermal and plasma-enhanced atomic layer deposition. Thin Solid Films, 2010, 519, 362-366.	1.8	57
66	Monolayered g-C3N4 nanosheet as an emerging cationic building block for bifunctional 2D superlattice hybrid catalysts with controlled defect structures. Applied Catalysis B: Environmental, 2020, 277, 119191.	20.2	56
67	Atomic layer deposition of Y2O3 and yttrium-doped HfO2 using a newly synthesized Y(iPrCp)2(N-iPr-amd) precursor for a high permittivity gate dielectric. Applied Surface Science, 2014, 297, 16-21.	6.1	54
68	Low-temperature Atomic Layer Deposition of TiO2, Al2O3, and ZnO Thin Films. Journal of the Korean Physical Society, 2011, 59, 452-457.	0.7	54
69	Zincâ€“Phosphorus Complex Working as an Atomic Valve for Colloidal Growth of Monodisperse Indium Phosphide Quantum Dots. Chemistry of Materials, 2017, 29, 6346-6355.	6.7	53
70	Molecular Identification of Cr(VI) Removal Mechanism on Vivianite Surface. Environmental Science & Technology, 2018, 52, 10647-10656.	10.0	53
71	Dynamic metal-polymer interaction for the design of chemoselective and long-lived hydrogenation catalysts. Science Advances, 2020, 6, eabb7369.	10.3	53
72	Atomic Layer Deposition ZnO:N Thin Film Transistor: The Effects of N Concentration on the Device Properties. Journal of the Electrochemical Society, 2010, 157, H214.	2.9	52

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73	Highly conductive and flexible fiber for textile electronics obtained by extremely low-temperature atomic layer deposition of Pt. NPG Asia Materials, 2016, 8, e331-e331.	7.9	51
74	Direct imprinting of MoS2 flakes on a patterned gate for nanosheet transistors. Journal of Materials Chemistry C, 2013, 1, 7803.	5.5	50
75	Activityâ€“Stability Relationship in Au@Pt Nanoparticles for Electrocatalysis. ACS Energy Letters, 2020, 5, 2827-2834.	17.4	49
76	Lattice Engineering to Simultaneously Control the Defect/Stacking Structures of Layered Double Hydroxide Nanosheets to Optimize Their Energy Functionalities. ACS Nano, 2021, 15, 8306-8318.	14.6	49
77	Highly Flexible Hybrid CMOS Inverter Based on Si Nanomembrane and Molybdenum Disulfide. Small, 2016, 12, 5720-5727.	10.0	46
78	Effect oxygen exposure on the quality of atomic layer deposition of ruthenium from bis(cyclopentadienyl)ruthenium and oxygen. Thin Solid Films, 2008, 516, 7345-7349.	1.8	45
79	Low Pressure Chemical Vapor Deposition of Aluminum-Doped Zinc Oxide for Transparent Conducting Electrodes. Journal of the Electrochemical Society, 2011, 158, D495.	2.9	45
80	A composite layer of atomic-layer-deposited Al2O3 and graphene for flexible moisture barrier. Carbon, 2017, 116, 553-561.	10.3	45
81	Porous Metalâ€“Organic Framework CUK-1 for Adsorption Heat Allocation toward Green Applications of Natural Refrigerant Water. ACS Applied Materials & Interfaces, 2019, 11, 25778-25789.	8.0	45
82	Atomic layer deposition ZnO:N flexible thin film transistors and the effects of bending on device properties. Applied Physics Letters, 2011, 98, .	3.3	44
83	Growth characteristics and properties of Ga-doped ZnO (GZO) thin films grown by thermal and plasma-enhanced atomic layer deposition. Applied Surface Science, 2014, 295, 260-265.	6.1	44
84	Optical and electrical properties of 2wt.% Al2O3-doped ZnO films and characteristics of Al-doped ZnO thin-film transistors with ultra-thin gate insulators. Thin Solid Films, 2010, 518, 2808-2811.	1.8	43
85	Nucleation and Growth of the HfO₂ Dielectric Layer for Graphene-Based Devices. Chemistry of Materials, 2015, 27, 5868-5877.	6.7	43
86	Plasma-Enhanced Atomic Layer Deposition of Cobalt Using Cyclopentadienyl Isopropyl Acetamidinato-Cobalt as a Precursor. Japanese Journal of Applied Physics, 2010, 49, 05FA10.	1.5	42
87	Catalytic chemical vapor deposition of large-area uniform two-dimensional molybdenum disulfide using sodium chloride. Nanotechnology, 2017, 28, 465103.	2.6	42
88	Low-temperature direct synthesis of high quality WS2 thin films by plasma-enhanced atomic layer deposition for energy related applications. Applied Surface Science, 2018, 459, 596-605.	6.1	42
89	Atomicâ€Layerâ€Depositionâ€Based 2D Transition Metal Chalcogenides: Synthesis, Modulation, and Applications. Advanced Materials, 2021, 33, e2005907.	21.0	42
90	Electronic Structure of Cerium Oxide Gate Dielectric Grown by Plasma-Enhanced Atomic Layer Deposition. Journal of the Electrochemical Society, 2011, 158, G217.	2.9	41

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91	Enhanced Light Stability of InGaZnO Thin-Film Transistors by Atomic-Layer-Deposited Y₂O₃ with Ozone. ACS Applied Materials & Interfaces, 2018, 10, 2143-2150.	8.0	41
92	Fe_xNi_{2â€“x}P Alloy Nanocatalysts with Electron-Deficient Phosphorus Enhancing the Hydrogen Evolution Reaction in Acidic Media. ACS Catalysis, 2020, 10, 11665-11673.	11.2	41
93	Electric Field Mediated Selectivity Switching of Electrochemical CO₂ Reduction from Formate to CO on Carbon Supported Sn. ACS Energy Letters, 2020, 5, 2987-2994.	17.4	41
94	Atomic Layer Deposition of Ruthenium and Ruthenium-oxide ThinFilms by Using a Ru(EtCp)$_{2}$ Precursor and Oxygen Gas. Journal of the Korean Physical Society, 2009, 55, 32-37.	0.7	41
95	Effect of Al₂O₃ Deposition on Performance of Top-Gated Monolayer MoS₂-Based Field Effect Transistor. ACS Applied Materials & Interfaces, 2016, 8, 28130-28135.	8.0	40
96	Uniform, large-area self-limiting layer synthesis of tungsten diselenide. 2D Materials, 2016, 3, 014004.	4.4	40
97	Atomic layer deposition of Y-stabilized ZrO2 for advanced DRAM capacitors. Journal of Alloys and Compounds, 2017, 722, 307-312.	5.5	40
98	Comparative study of the growth characteristics and electrical properties of atomic-layer-deposited HfO₂ films obtained from metal halide and amide precursors. Journal of Materials Chemistry C, 2018, 6, 7367-7376.	5.5	40
99	Plasma-Enhanced Atomic Layer Deposition of Ni. Japanese Journal of Applied Physics, 2010, 49, 05FA11.	1.5	38
100	High-Throughput Screening to Investigate the Relationship between the Selectivity and Working Capacity of Porous Materials for Propylene/Propane Adsorptive Separation. Journal of Physical Chemistry C, 2016, 120, 24224-24230.	3.1	37
101	Input Voltage Mapping Optimized for Resistive Memory-Based Deep Neural Network Hardware. IEEE Electron Device Letters, 2017, 38, 1228-1231.	3.9	37
102	Superior role of MXene nanosheet as hybridization matrix over graphene in enhancing interfacial electronic coupling and functionalities of metal oxide. Nano Energy, 2018, 53, 841-848.	16.0	36
103	Out-of-plane piezoresponse of monolayer MoS2 on plastic substrates enabled by highly uniform and layer-controllable CVD. Applied Surface Science, 2019, 487, 1356-1361.	6.1	36
104	Atomic Layer Deposition of Ru Thin Films Using a Ru(0) Metallorganic Precursor and O₂. ECS Journal of Solid State Science and Technology, 2013, 2, P47-P53.	1.8	35
105	Highly-conformal p-type copper(I) oxide (Cu2O) thin films by atomic layer deposition using a fluorine-free amino-alkoxide precursor. Applied Surface Science, 2015, 349, 673-682.	6.1	35
106	The effect of La2O3-incorporation in HfO2 dielectrics on Ge substrate by atomic layer deposition. Applied Surface Science, 2013, 287, 349-354.	6.1	34
107	The electrical properties of low pressure chemical vapor deposition Ga doped ZnO thin films depending on chemical bonding configuration. Applied Surface Science, 2014, 297, 125-129.	6.1	34
108	Atomic Layer Deposition of Co Using N2â•H2 Plasma as a Reactant. Journal of the Electrochemical Society, 2011, 158, H1179.	2.9	33

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109	Spontaneous Formation of Vertical Magneticâ€Metalâ€Nanorod Arrays During Plasmaâ€Enhanced Atomic Layer Deposition. Small, 2008, 4, 2247-2254.	10.0	32
110	Photocatalytic effect of thermal atomic layer deposition of TiO2 on stainless steel. Applied Catalysis B: Environmental, 2011, 104, 6-11.	20.2	32
111	n-ZnO:N/p-Si nanowire photodiode prepared by atomic layer deposition. Applied Physics Letters, 2012, 100, .	3.3	32
112	Growth characteristics and electrical properties of SiO2 thin films prepared using plasma-enhanced atomic layer deposition and chemical vapor deposition with an aminosilane precursor. Journal of Materials Science, 2016, 51, 5082-5091.	3.7	31
113	Growth Characteristics and Film Properties of Cerium Dioxide Prepared by Plasma-Enhanced Atomic Layer Deposition. Journal of the Electrochemical Society, 2011, 158, G169.	2.9	30
114	Molecular oxidation of surface â€“CH3 during atomic layer deposition of Al2O3 with H2O, H2O2, and O3: A theoretical study. Applied Surface Science, 2018, 457, 376-380.	6.1	29
115	uMBD: A Materials-Ready Dispersion Correction That Uniformly Treats Metallic, Ionic, and van der Waals Bonding. Journal of the American Chemical Society, 2020, 142, 2346-2354.	13.7	29
116	Synthesis of a Hybrid Nanostructure of ZnO-Decorated MoS₂ by Atomic Layer Deposition. ACS Nano, 2020, 14, 1757-1769.	14.6	29
117	Flat band voltage (VFB) modulation by controlling compositional depth profile in La2O3/HfO2 nanolaminate gate oxide. Journal of Applied Physics, 2010, 107, 074109.	2.5	27
118	Selectivity Modulated by Surface Ligands on Cu₂O/TiO₂ Catalysts for Gas-Phase Photocatalytic Reduction of Carbon Dioxide. Journal of Physical Chemistry C, 2019, 123, 29184-29191.	3.1	27
119	Low-temperature, high-growth-rate ALD of SiO2 using aminodisilane precursor. Applied Surface Science, 2019, 485, 381-390.	6.1	27
120	Atomic layer deposition of B2O3/SiO2 thin films and their application in an efficient diffusion doping process. Journal of Materials Chemistry C, 2014, 2, 5805.	5.5	26
121	Thermodynamics of Multicomponent Perovskites: A Guide to Highly Efficient and Stable Solar Cell Materials. Chemistry of Materials, 2020, 32, 4265-4272.	6.7	26
122	?The Degradation of Deposition Blocking Layer during Area Selective Plasma Enhanced Atomic Layer Deposition of Cobalt. Journal of the Korean Physical Society, 2010, 56, 104-107.	0.7	26
123	Nitride mediated epitaxy of CoSi2 through self-interlayer-formation of plasma-enhanced atomic layer deposition Co. Applied Physics Letters, 2007, 90, 213509.	3.3	25
124	The Effects of Ultraviolet Exposure on the Device Characteristics of Atomic Layer Deposited-ZnO:N Thin Film Transistors. Journal of the Electrochemical Society, 2011, 158, J150-J154.	2.9	25
125	Low temperature atomic layer deposited Al-doped ZnO thin films and associated semiconducting properties. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2012, 30, 031210.	1.2	25
126	Synthesis of two-dimensional MoS2/graphene heterostructure by atomic layer deposition using MoF6 precursor. Applied Surface Science, 2019, 494, 591-599.	6.1	25

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127	Phase-controlled synthesis of SnOx thin films by atomic layer deposition and post-treatment. Applied Surface Science, 2019, 480, 472-477.	6.1	25
128	Atomic layer deposition of a uniform thin film on two-dimensional transition metal dichalcogenides. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	25
129	Comparative study on atomic layer deposition of HfO₂via substitution of ligand structure with cyclopentadiene. Journal of Materials Chemistry C, 2020, 8, 1344-1352.	5.5	24
130	Dynamic Transformation of a Ag⁺-Coordinated Supramolecular Nanostructure from a 1D Needle to a 1D Helical Tube via a 2D Ribbon Accompanying the Conversion of Complex Structures. Journal of the American Chemical Society, 2021, 143, 3113-3123.	13.7	24
131	Plasma-enhanced atomic layer deposition of Co using Co(MeCp)2 precursor. Journal of Energy Chemistry, 2013, 22, 403-407.	12.9	23
132	Multiscale Simulation Method for Quantitative Prediction of Surface Wettability at the Atomistic Level. Journal of Physical Chemistry Letters, 2018, 9, 1750-1758.	4.6	23
133	Growth characteristics and electrical properties of Ta2O5 grown by thermal and O3-based atomic layer deposition on TiN substrates for metalâ€“insulatorâ€“metal capacitor applications. Thin Solid Films, 2013, 542, 71-75.	1.8	22
134	Coupled self-assembled monolayer for enhancement of Cu diffusion barrier and adhesion properties. RSC Advances, 2014, 4, 60123-60130.	3.6	22
135	Hybrid nanofabrication processes utilizing diblock copolymer nanotemplate prepared by self-assembled monolayer based surface neutralization. Journal of Vacuum Science & Technology B, 2008, 26, 189.	1.3	20
136	Photocatalytic activities of TiO2 thin films prepared on Galvanized Iron substrate by plasma-enhanced atomic layer deposition. Thin Solid Films, 2010, 518, 4757-4761.	1.8	20
137	In situ surface cleaning on a Ge substrate using TMA and MgCp₂for HfO₂-based gate oxides. Journal of Materials Chemistry C, 2015, 3, 4852-4858.	5.5	20
138	Simultaneous Enhanced Efficiency and Stability of Perovskite Solar Cells Using Adhesive Fluorinated Polymer Interfacial Material. ACS Applied Materials & Interfaces, 2021, 13, 35595-35605.	8.0	20
139	Initial Stage Growth during Plasmaâ€Enhanced Atomic Layer Deposition of Cobalt. Chemical Vapor Deposition, 2012, 18, 41-45.	1.3	19
140	Growth characteristics and properties of indium oxide and indium-doped zinc oxide by atomic layer deposition. Thin Solid Films, 2015, 587, 83-87.	1.8	19
141	Nitrogen-doped ZnO/n-Si coreâ€“shell nanowire photodiode prepared by atomic layer deposition. Materials Science in Semiconductor Processing, 2015, 33, 154-160.	4.0	19
142	Surface-Localized Sealing of Porous Ultralow-k Dielectric Films with Ultrathin (<2 nm) Polymer Coating. ACS Nano, 2017, 11, 7841-7847.	14.6	19
143	The Impact of an Ultrathin Y₂O₃Layer on GeO₂Passivation in Ge MOS Gate Stacks. IEEE Transactions on Electron Devices, 2017, 64, 3303-3307.	3.0	19
144	Synthesis and Application of AgBiS₂ and Ag₂S Nanoinks for the Production of IR Photodetectors. ACS Omega, 2021, 6, 20710-20718.	3.5	19

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145	Atomic layer deposition of transition metals for silicide contact formation: Growth characteristics and silicidation. Microelectronic Engineering, 2013, 106, 69-75.	2.4	18
146	Significant Enhancement of the Dielectric Constant through the Doping of <scp><scp>CeO</scp></scp>₂ into <scp><scp>HfO</scp></scp>₂ by Atomic Layer Deposition. Journal of the American Ceramic Society, 2014, 97, 1164-1169.	3.8	18
147	Growth of highly conformal ruthenium-oxide thin films with enhanced nucleation by atomic layer deposition. Journal of Alloys and Compounds, 2014, 610, 529-539.	5.5	18
148	Effects of Cl-Based Ligand Structures on Atomic Layer Deposited HfO₂. Journal of Physical Chemistry C, 2016, 120, 5958-5967.	3.1	18
149	Structural and electrical properties of Ge-doped ZrO2 thin films grown by atomic layer deposition for high-k dielectrics. Journal of Materials Science, 2018, 53, 15237-15245.	3.7	18
150	Thickness-dependent electrochemical response of plasma enhanced atomic layer deposited WS2 anodes in Na-ion battery. Electrochimica Acta, 2019, 322, 134766.	5.2	18
151	Hydrogen barrier performance of sputtered La2O3 films for InGaZnO thin-film transistor. Journal of Materials Science, 2019, 54, 11145-11156.	3.7	18
152	Electrical Properties of Atomic Layer Deposition HfO[sub 2] and HfO[sub x]N[sub y] on Si Substrates with Various Crystal Orientations. Journal of the Electrochemical Society, 2008, 155, H267.	2.9	17
153	High efficiency n-ZnO/p-Si coreâ€“shell nanowire photodiode based on well-ordered Si nanowire array with smooth surface. Materials Science in Semiconductor Processing, 2014, 27, 297-302.	4.0	17
154	ZnO homojunction coreâ€“shell nanorods ultraviolet photo-detecting diodes prepared by atomic layer deposition. Sensors and Actuators A: Physical, 2014, 210, 197-204.	4.1	17
155	Optimization and device application potential of oxideâ€“metalâ€“oxide transparent electrode structure. RSC Advances, 2015, 5, 65094-65099.	3.6	17
156	Fabrication of single-phase SnS film by H2 annealing of amorphous SnSx prepared by atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	2.1	17
157	Cluster Expansion Method for Simulating Realistic Size of Nanoparticle Catalysts with an Application in CO₂ Electroreduction. Journal of Physical Chemistry C, 2018, 122, 9245-9254.	3.1	17
158	Input-Splitting of Large Neural Networks for Power-Efficient Accelerator with Resistive Crossbar Memory Array. , 2018, , .		17
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